



MAIL STOP AF
PATENT
8017-1096

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Yasuaki TSUCHIYA et al.

Conf. 4719

Application No. 10/622,735

Group 1755

Filed July 21, 2003

Examiner: M. Marcheschi

SLURRY FOR POLISHING COPPER-BASED
METAL

FURTHER SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

August 1, 2005

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying documents, copies of which are attached to this statement, are made of record on the enclosed Form PTO-1449.

A concise explanation of the relevance of these items is that these references were cited in an Office Action dated June 22, 2005 in the corresponding Japanese application No. 2002-225734. A copy of the Official Action in which they were cited is attached hereto, with what is believed to be the pertinent portion enclosed in a wavy line. **An English translation of the enclosed portion is also attached hereto.**

Respectfully submitted,

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Y&T August 1, 2005

TSUCHIYA et al.
U.S. Application No. 10/622,735
Our Ref. 8017-1096

Reason 1

Claims 1-6
Citation 1

Remarks:

In Citation 1 (reference Sections [0008], [0024], and [0072]), reference is made to an abrasive slurry which has inclusions of a silica polishing agent (colloidal silica), an oxide agent (hydrogen peroxide), amino acid (glycine), and a triazole type compound (1, 2, 4 - triazole), and in which the mass ratio of the amino acid /triazole type compound is approximately 6.7 (=2/0.3).

Reason 2

Claims 1-6
Citation 1

Remarks:

Reference is made to Reason 1.

Reference Citation List

1. Japanese Laid Open Patent Publication 2002-164308

Record of the Examination Results relating to Documents of
the Prior Art

- Examined Technical Field: IPC 7th Edition

H01L21/304

The record of the examination results relating to documents of the prior art does not constitute the grounds for rejection.